# of Book: Handbook of Thin Film Process Technology

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Title of Book: Handbook of Thin Film Process Technology
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Abstract / Description: The Handbook of Thin Film Process Technology is a practical handbook for the thin film scientist, engineer and technician. The main work is regularly updated with new material, and this volume is a special issue on substrate cleaning which will be of interest to industrial and academic researchers in the semiconductor and optics industry in addition to owners of the main Handbook. This supplement includes recipes which give precise instructions for the cleaning of specific substrates, for specific film depositions, or using specific techniques. In addition, general articles evaluate the cleaning procedure, covering the usual contaminants, handling and storage of substrates, chemicals (for instance the importance of the pH of solution, particle deposition), DI quality (level of contamination, water drops), what is removed, drying (e.g. the Marangoni effect), and the surface of the substrate before deposition (composition, morphology, hydrophilic, hydrophobic). Keywords: G1 Cleaning of silicon for ULSI and CVD (Huang); G2 Chemical composition and morphology of silicon surfaces (K Jacobi); G3 Surface analyses of substrates for microelectronic device fabrication (Berbezier); plus nine recipes for film deposition for electronic applications: Wet chemical cleaning of Si for IC manufacturing (Christernson and Butterbaugh); Cleaning of SiC and Al203 substrates for MBE and MOCVD deposition of AlN, GaN and InAlGaN (Kouvetakis); Cleaning of II-VI substrates for for MBE and MOCVD deposition (N Magnea); Dry cleaning of silicon (plasma, UV-ozone, atomic H) (I Eisele); Vapor phase cleaning (Butterbaugh); Wet chemical etching of GAS and InP for MOCVD deposition of III-V (Mason); Wet chemical etching of Si for MBE and GSMBE of Si and SiGeC (ex-situ and in-situ) (Le Thanh); Wet chemical etching of Si for CVD of Si and SiGeC (Tillack).
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This book is a comprehensive reference focusing on thin film technologies and applications used in the semiconductor industry and the closely related areas of thin film deposition, thin film micro properties, photovoltaic solar energy applications, new materials for memory applications and methods for thin film optical processes. In a major restructuring, this edition of the handbook lays the foundations with an up-to-date treatment of lithography, contamination and yield management, and reliability of thin films. The established physical and chemical deposition processes and Buy paper book Convert (EPUB, MOBI) Sent to Email Sent to Kindle Report. â€œ You miss 100% of the shots you donâ€™t take. â€ â€• Wayne Gretzky. Similar Free eBooks. Filter by page count 1-24 Pages 25-50 Pages 51-100 Pages 100+ Pages. The Gifts of Imperfection: Embrace Who You Are.Â handbook of thin-film deposition processes and techniques. 646 PagesÂ·2009Â·6.02 MBÂ·502 Downloads. Library of Congress Cataloging-in-Publication Data. Handbook of Thin-Film Deposition Pro ...Â processes and fields. The fundamental problem of stochastic dynamics is to identify the essential Dietary Reference Intakes. 306 PagesÂ·2001Â·886 KBÂ·13,681 DownloadsÂ·New! Since 1994, the Institute of Medicine's Food and Nutrition Board has been involved in developing